

INFORMATION DISCLOSURE STATEMENT BY APPLICANT

Application Number

First Named Inventor

Filing Date

Complete if Known

Robert Bristol

September 30, 2003

10/676,411

NON PATENT LITERATURE DOCUMENTS					
Examiner Initials*	Cite No.1	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T²		
		THOMAS, M.D.R., et al., "Electron-Beam Exposure Characteristics of a novel Ru-PMMA Composite Resist, Microelectronic Eng., 41/42 pp 327-330, 1998.			
		NAKANO, Atsuro, et al., "Dependence of Acid Yield on Acid Generator in Chem. Amplified Resist for Post-Optical Lith.", Japan J. of Applied Phys., vol. 44, no. 7B, 5832-5835, 2005			

Examiner	Date	X
Signature	Considered	

^{*}Examiner: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication.

^{&#}x27;Applicant's unique citation designation number. 'Applicant is to place a check mark here if English language Translation is attached.